Amendments to the Claims:

This listing of claims will replace all prior versions and listings of claims in the application:

Listing of Claims:

Claims 1-15 are cancelled.

16.(currently amended) A method for fabricating a magnetic tunnel junction (MTJ) cell, said cell having a narrow dimension at its middle whereat artificial nucleation sites for magnetization switching are formed and said cell having an easy axis of magnetization passing longitudinally through said middle, thereby producing a fanning mode of magnetization vectors at opposite peripheral edges of said cell and, as a result, said cell having a lowered switching field threshold and a reduced sensitivity to defects and shape irregularities comprising:

forming an MTJ layered stack, the magnetic layers of said stack having a common crystalline anisotropy and common easy axis of magnetization;

patterning within said stack, by photolithography photolithography and ion-milling methods, at least one MTJ cell having a narrow dimension at its middle, said dimension being transverse to the direction of said easy axis of magnetization.

17.(original) The method of claim 16 wherein the method of forming the MTJ stack further comprises:

forming a ferromagnetic free layer;

forming an insulating tunneling layer on said free layer;

forming a multi-layered magnetically pinned layer on said tunneling layer, said pinned layer formation further comprising:

forming a first ferromagnetic layer adjacent to said tunneling layer; forming a non-magnetic coupling layer on said first ferromagnetic layer; forming a second ferromagnetic layer on said coupling layer;

forming an antiferromagnetic pinning layer on said second ferromagnetic layer, wherein said multi-layered magnetically pinned layer has a net magnetic moment which is substantially zero as a result of the magnetic moments of said first and second ferromagnetic layers being substantially equal and strongly magnetically coupled in an anti-parallel configuration.

18.(original) The method of claim 17 wherein said free magnetic layer is formed as a multilayer comprising a third and fourth ferromagnetic layer separated by a non magnetic spacer layer and wherein the magnetizations of said ferromagnetic layers may be weakly or strongly coupled in antiparallel directions.